

L Number	Hits	Search Text	DB	Time stamp
1	89	((((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (silicon adj oxynitride or "SiON" or titanium adj nitride or "Ti.sub."?"N.sub."? or "TiN" or "Ti" adj "N")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 10:52
2	20	((((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4) not (((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (silicon adj oxynitride or "SiON" or titanium adj nitride or "Ti.sub."?"N.sub."? or "TiN" or "Ti" adj "N"))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 11:13
3	86	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) not (((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 11:16
4	816	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) not (((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 11:24
5	9	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) with (via or hole or wall or sidewall or opening or trench)) and 427/97.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/30 17:01

6	0	430/311,313,317,950.ccls. and (DARC or TARC or BARC or ARC or antireflect\$4 or anti adj reflect\$4) near5 (sidewall or side adj wall or hole adj wall or via near2 wall or via near2 side or trench near2 wall or trench near2 side or conformal\$3) same (IMD or ILD or dielectric) not ((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:03
7	0	430/311,313,317,950.ccls. and (DARC or TARC or BARC or ARC or antireflect\$4 or anti adj reflect\$4) near5 (sidewall or side adj wall or hole adj wall or via near2 wall or via near2 side or trench near2 wall or trench near2 side or conformal\$3) and (IMD or ILD or dielectric) not ((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:04
8	0	(430/311,313,317,950.ccls. and (DARC or TARC or BARC or ARC or antireflect\$4 or anti adj reflect\$4) near5 (sidewall or side adj wall or hole adj wall or via near2 wall or via near2 side or trench near2 wall or trench near2 side or conformal\$3) and (IMD or ILD or dielectric) not ((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:06
-	2	("6297168" or ("6383943")).PN.	USPAT; US-PGPUB	2003/01/27 14:02
-	883	(BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/21 18:45
-	169	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/18 17:10
-	94	(((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/18 17:12
-	75	(((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (silicon adj oxynitride or "SiON" or titanium adj nitride or "Ti.sub.?" "N.sub.?" or "TiN" or "Ti" adj "N")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 10:51

-		19	((((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4) not (((((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (silicon adj oxynitride or "SiON" or titanium adj nitride or "Ti.sub."?"N.sub."? or "TiN" or "Ti" adj "N"))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 11:12
-		75	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) not (((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) same etch\$3 near2 stop\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 11:15
-		714	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) not (((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)) and (BARC or ARC or antireflect\$4 or anti adj reflect\$4) near3 (conformal or via or opening or trench or groove or sidewall))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 11:23
-		42789	(BARC or ARC or antireflect\$4 or anti adj reflect\$4) with (via or hole or wall or sidewall or opening or trench)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/21 10:18
-		9	((BARC or ARC or antireflect\$4 or anti adj reflect\$4) with (via or hole or wall or sidewall or opening or trench)) and 427/97.cc1s.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:00
-		1	("6541367").PN.	USPAT; US-PGPUB	2003/04/21 16:17
-		0	430/311,313,317,950.cc1s. and (DARC or TARC or BARC or ARC or antireflect\$4 or anti adj reflect\$4) near5 (sidewall or side adj wall or hole adj wall or via near2 wall or via near2 side or trench near2 wall or trench near2 side or conformal\$3) same (IMD or ILD or dielectric) not ((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:01

-	0	430/311,313,317,950.ccls. and (DARC or TARC or BARC or ARC or antireflect\$4 or anti adj reflect\$4) near5 (sidewall or side adj wall or hole adj wall or via near2 wall or via near2 side or trench near2 wall or trench near2 side or conformal\$3) and (IMD or ILD or dielectric) not ((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:01
-	0	(430/311,313,317,950.ccls. and (DARC or TARC or BARC or ARC or antireflect\$4 or anti adj reflect\$4) near5 (sidewall or side adj wall or hole adj wall or via near2 wall or via near2 side or trench near2 wall or trench near2 side or conformal\$3) and (IMD or ILD or dielectric) not ((BARC or ARC or antireflect\$4 or anti adj reflect\$4) same (resist or photoresist) same (IMD or dielectric)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/30 17:01